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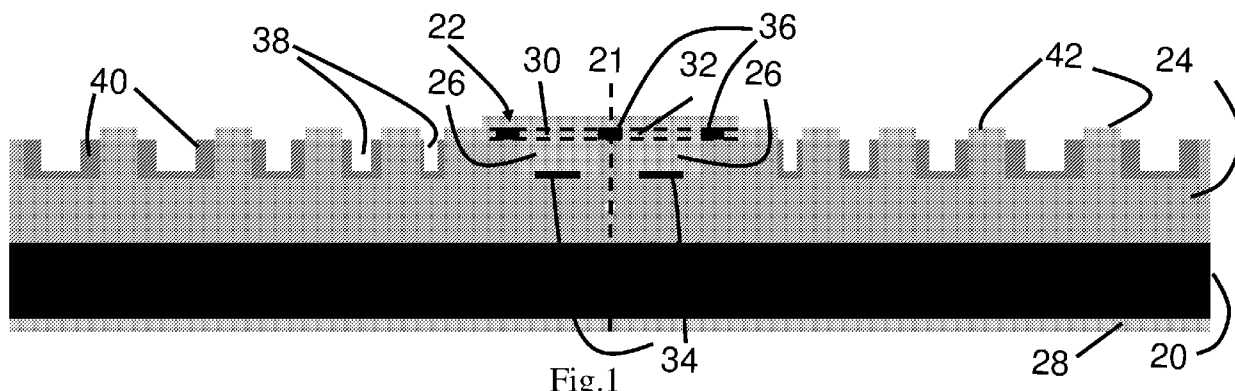


Fig.1

(57) Abstract: A silicon carbide diode that contains a silicon carbide substrate (20), a silicon carbide layer (24) on top of the silicon carbide substrate, two first lower barrier metal portions (36) disposed on the silicon carbide layer and separated from each other along a top surface of the silicon carbide layer, and a first higher barrier metal portion (30) connected to the two lower barrier metal portions. The silicon carbide layer is thinner and having lower doping than the silicon carbide substrate. The first higher barrier metal portion is located between the two first lower barrier metal portions on the silicon carbide layer along a direction of the top surface of the silicon carbide layer. By reducing the leakage current at the junction barrier, the reverse breakdown voltage of the silicon carbide diode is significantly improved.



High Voltage Power Device with Hybrid Schottky Trenches and Method of Fabricating the Same

FIELD OF INVENTION

[0001] This invention relates to semiconductor devices, and in particular to silicon carbide diodes.

BACKGROUND OF INVENTION

[0002] Silicon Carbide (SiC) devices belong to the so-called wide band gap semiconductor group, and they offer a number of attractive characteristics for high voltage power semiconductors when compared to commonly used silicon (Si). In particular, the much higher breakdown field strength and thermal conductivity of SiC make them essential for power electronics systems. These diodes have static performances comparable to those manufactured from silicon. Moreover, silicon carbide based Schottky diodes do not suffer from switching losses.

[0003] However, existing silicon carbide diodes often suffer from other problems including but not limited to large leakage current and low reverse breakdown voltage, which deteriorate the performance of the silicon carbide diodes. If the diode leakage current is high, the blocking voltage will be low. Therefore, improvement of leakage current is needed for higher blocking voltage applications.

SUMMARY OF INVENTION

[0004] In the light of the foregoing background, it is an object of the present invention to provide an alternate silicon carbide diode array which eliminates or at least alleviates the above technical problems.

[0005] The above object is met by the combination of features of the main claim; the sub-claims disclose further advantageous embodiments of the invention.

[0006] One skilled in the art will derive from the following description other objects of the invention. Therefore, the foregoing statements of object are not exhaustive and serve merely to illustrate some of the many objects of the present invention.

[0007] Accordingly, the present invention, in one aspect is a silicon carbide diode that contains a silicon carbide substrate, a silicon carbide layer on top of the silicon carbide substrate, two first lower barrier metal portions disposed on the silicon carbide layer and separated from each other along a top surface of the silicon carbide layer, and a first higher barrier metal portion connected to the two lower barrier metal portions. The silicon carbide layer is thinner and having lower doping than the silicon carbide substrate. The first higher barrier metal portion is located between the two first lower barrier metal portions on the silicon carbide layer along a direction of the top surface of the silicon carbide layer.

[0008] Preferably, the silicon carbide diode further includes a second higher barrier metal portion. The first and second higher barrier metal portions are configured with the two first lower barrier metal portions in an alternating manner at the top surface of the silicon carbide layer, such that the first higher barrier metal portion and the second higher barrier metal portion are separated by one of the two first lower barrier metal portions.

[0009] More preferably, the first higher barrier metal portion and the second higher barrier metal portion further extend downwardly into the silicon carbide layer to form two first trenches.

[0010] Most preferably, the silicon carbide diode further contains second lower barrier metal portions located at the bottom ends of the first trenches.

[0011] According to a variation of the preferred embodiments, the silicon carbide diode further contains a higher barrier metal cap, which together with the silicon carbide layer, fully encapsulates the first lower barrier metal portions.

[0012] According to another variation of the preferred embodiments, the first higher barrier metal portion further extends downwardly into the silicon carbide layer to form a first trench.

[0013] According to a further variation of the preferred embodiments, the silicon carbide diode further contains a second trench separated from an active region defined by the first higher barrier metal portion and the two first lower barrier metal portions. The second trench is formed by a dielectric material.

[0014] Preferably, the silicon carbide diode further contains a plurality of the second trenches which are separated from each other. Each second trench forms a closed shape when viewing from above.

[0015] More preferably, the plurality of the second trenches forms a plurality of concentric rings.

[0016] According to a further variation of the preferred embodiments, the plurality of the second trenches is separated from each other by one or more third higher barrier metal portions.

[0017] According to a further variation of the preferred embodiments, the silicon carbide diode further contains an aluminum compound buffer as an interface between the second trench and the silicon carbide layer.

[0018] According to another aspect of the invention, there is disclosed a silicon carbide diode which contains a silicon carbide substrate, a silicon carbide layer on top of the silicon carbide substrate, an active region defined by at least one barrier metal which is formed on the silicon carbide layer; and a plurality of trenches formed inside the silicon carbide layer, and separated from the active region along a direction of a top surface of the silicon carbide layer. The silicon carbide layer is thinner and having lower doping than the silicon carbide substrate. Each trench forms a closed shape when viewing from above; and each trench is formed by a dielectric material. There is further a plurality of the barrier metal formed on the silicon carbide layer outside the active region; wherein

each said barrier metal forming a closed shape and being located in between two of the plurality of trenches in when viewing from above.

[0019]

[0020] Preferably, the silicon carbide diode further contains an aluminum compound buffer at an interface between the second trench and the silicon carbide layer.

[0021] According to another aspect of the invention, there is disclosed a method of producing a silicon carbide diode. The method includes the steps of providing a silicon carbide layer on top of a silicon carbide substrate, forming a first trench and a second trench inside the silicon carbide layer, depositing a lower barrier metal on a top surface of the silicon carbide layer in the active region, which covers the first trench, an depositing a higher barrier metal on the top surface of the silicon carbide layer in the active region, which covers the first trench. The first trench is a part of an active region of the silicon carbide diode. The second trench is separated from the first trench. The silicon carbide layer is thinner and having lower doping than the silicon carbide substrate.

[0022] Preferably, the forming step above further includes forming a plurality of second trenches that are separated from the first trench and from each other, each said second trench forming a closed shape.

[0023] More preferably, the step of depositing a higher barrier metal above further contains depositing the higher barrier metal on portions of the silicon carbide layer surrounding openings of the plurality of second trenches.

[0024] According to a variation of the preferred embodiments, the step of forming a first trench and a second trench further contains forming a plurality of first trenches that are separated from the second trench, and from each other by at least one portion of the silicon carbide layer.

[0025] According to another variation of the preferred embodiments, the step of depositing a lower barrier metal further contains the step of depositing the lower barrier

metal on a bottom surface of the first trench, as well as on portions of the silicon carbide layer surrounding an opening of the first trench.

[0026] According to a further variation of the preferred embodiments, the method further contains the step of filling the first trench with the higher barrier metal.

[0027] According to a further variation of the preferred embodiments, the method further contains the step of filling the second trench with a dielectric material.

[0028] According to a further variation of the preferred embodiments, the method further contains the step of forming a buffer layer at the interface between the second trench and the silicon carbide layer.

[0029] One can see therefore that the silicon carbide diode in the invention contains a number of innovative changes to the semiconductor structure, each of which helping with reducing the leakage current at the junction barrier. When these innovative changes are combined the resultant silicon carbide diode has a significantly smaller leakage current compared to conventional devices, thus achieving a higher block voltage. For example, forming trenches in the silicon carbide layer and filling them with dielectric materials reduces the electrical field at the junction barrier and the leakage current, but adding a buffer layer further alleviates the current leakage. Similarly, forming multiple trenches around the active region, and forming multiple hybrid Schottky trenches within the active region both help reducing the leakage current at the junction barrier. It should be noted that the innovative changes can be used freely in any combinations thereof although the best performance is achieved using the configuration in the most preferred embodiment.

[0030] In addition, the manufacturing method of the proposed silicon carbide diode in the invention is advantageous not only because of a cost reduction compared to conventional processes, but more importantly the technique of depositing trench metal in a self-aligned way and the technique of void free termination filling help achieve a reduction in leakage current and a high breakdown voltage, while keeping the manufacturing cost relatively low. In comparison, ion implantation used in conventional art to achieve similar metal deposition effect is much costlier.

BRIEF DESCRIPTION OF FIGURES

[0031] The foregoing and further features of the present invention will be apparent from the following description of preferred embodiments which are provided by way of example only in connection with the accompanying figures, of which:

[0032] Fig. 1 is the cross-sectional illustration of a silicon carbide diode according to a first embodiment of the present invention.

[0033] Fig. 2a is a top view of the layout of the silicon carbide diode in Fig. 1 showing second trenches and high barrier metals.

[0034] Fig. 2b is a simplified top view of the silicon carbide diode in Fig. 1 showing only the layout of barrier metals.

[0035] Fig. 3a shows the comparison of experimental results of reverse breakdown voltages of silicon carbide diodes using SiO_2 as passivation and Al_2O_3 as passivation respectively.

[0036] Fig. 3b shows the comparison of experimental results of leakage currents of silicon carbide diodes using SiO_2 as passivation and Al_2O_3 as passivation respectively.

[0037] Fig. 4 is an illustration of the leakage current flows in the active region of the silicon carbide diode of Figs. 1-2b.

[0038] Figs. 5a-5j show the method steps of one method which can be used to form the silicon carbide diode array in Fig. 1.

[0039] Figs. 6a-6d show the cross-sectional illustrations of silicon carbide diodes according to some other embodiments of the invention.

[0040] In the drawings, like numerals indicate like parts throughout the several embodiments described herein.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

[0041] In the claims which follow and in the preceding description of the invention, except where the context requires otherwise due to express language or necessary implication, the word “comprise” or variations such as “comprises” or “comprising” is used in an inclusive sense, i.e. to specify the presence of the stated features but not to preclude the presence or addition of further features in various embodiments of the invention.

[0042] As used herein and in the claims, “couple” or “connect” refers to electrical coupling or connection either directly or indirectly via one or more electrical means unless otherwise stated.

[0043] Terms such as “horizontal”, “vertical”, “upwards”, “downwards”, “above”, “below” and similar terms as used herein are for the purpose of describing the invention in its normal in-use orientation and are not intended to limit the invention to any particular orientation.

[0044] Referring now to Figs. 1-2b, the first embodiment of the present invention is a silicon carbide diode of Schottky type, which contains a silicon carbide substrate **20** as the underlying structure of the device. As skilled persons would understand, the silicon carbide substrate **20** is made from SiC wafers, and the silicon carbide substrate **20** is of n+ type. On top of the silicon carbide substrate **20**, there is a silicon carbide epitaxial layer **24** of n- type. The silicon carbide layer **24** is thinner and has lower doping than the silicon carbide substrate **20**.

[0045] Underneath the silicon carbide substrate **20**, there is a layer of ohmic metal **28** forming a cathode of the silicon carbide diode. On the other side, at a center area of the device there are also junction barrier metals forming an anode of the silicon carbide diode. In particular, two different types of barrier metals, including a high barrier metal and a lower barrier metal, form hybrid Schottky metals of the silicon carbide diode in this embodiment. As shown in Fig. 1, around a central axis **21** that is defined for the entire

silicon carbide diode which extends vertically, there are at least two first trenches **26** formed respectively by a first high barrier metal portion **30** and a second high barrier metal portion **32** (as shown by portions enclosed by two parallel dashed lines) extending downwardly into the silicon carbide layer **24**. In other words, the first trenches **26** are filled with a high barrier metal. The two first trenches **26** preferably have the same dimensions. At the bottom of each first trenches **26** there is arranged a second lower barrier metal portion **34** that has a substantially strip shape. The second lower barrier metal portion **34** is also separated from the sidewall **26a** of the first trench **26** (as shown in Fig. 4). In addition, on a top surface of the silicon carbide layer **24** surrounding the two first trenches **26**, there are a number of first lower barrier metal portions **36** along a direction of the top surface of the silicon carbide layer **24**. In Fig. 1 there are shown three such first lower barrier metal portions **36** and they are separated from each other. Each first lower barrier metal portion **36** has a width substantially the same as that of a first trench **26**, and the width is larger than the depth of the first trench **26**. In particular, between each two adjacent first lower barrier metal portions **36** there is either the first high barrier metal portion **30** or the second high barrier metal portion **32**. The first high barrier metal portion **30** and the second high barrier metal portion **32** are therefore configured with the plurality of first lower barrier metal portions **36** in an alternating manner, and they are positioned along a same horizontal line (not shown). Note that the first lower barrier metal portions **36** are both offset from the second lower barrier metal portion **34** along a vertical direction and along a horizontal direction.

[0046] In addition, there is a higher barrier metal cap **22** formed on top of the first high barrier metal portion **30**, the second high barrier metal portion **32** and the plurality of first lower barrier metal portions **36**. The cap **22** together with the silicon carbide layer **24** fully encapsulates the first high barrier metal portion **30**, the second high barrier metal portion **32** and the plurality of first lower barrier metal portions **36**. In addition, although different part numbers are used for description of this embodiment, the higher barrier metal cap **22**, the first high barrier metal portion **30**, the second high barrier metal portion **32** and the two first trenches **24** all consist of the same high barrier metal so they together form an integral piece of material. The different part numbers are used only for the

purpose of easy understanding of the geometrical structure of the Schottky barrier metals of the silicon carbide diode. The first high barrier metal portion **30**, the second high barrier metal portion **32**, the two first trenches **36** (with the second lower barrier metal portions **34**) and the plurality of first lower barrier metal portions **36** together form an active region of the silicon carbide diode.

[0047] The higher barrier metal and lower barrier metal can be any suitable type of metal which attains to form a Schottky junction with the silicon carbide layer **24** and silicon carbide substrate **20**. Examples of such materials include Titanium (Ti), Nickel (Ni), Titanium nitride (TiN), Titanium aluminum (TiAl), Platinum (Pt) and the like. However, as their plain meanings suggest the higher barrier metal in the silicon carbide diode should create a stronger junction barrier than the lower barrier metal.

[0048] Outside of the active region, in the silicon carbide layer **24** there are formed a plurality of second trenches **38** each filled with a dielectric material (not shown in Fig. 1). In Fig. 1, the number of second trenches **38** on the two sides of the active region is the same and the second trenches **38** are symmetrically arranged around the active region. The second trenches **38**, similar to the first trenches **36** described above, extend downwardly from the top surface of the silicon carbide layer **24**. The second trenches **38** and the first trenches **36** have substantially the same depth. However, one can see that along the horizontal direction of the top surface of the silicon carbide layer **24**, different second trenches **38** have different width, and those closer to the active region have smaller widths compared to those further away from the active region. Inside the silicon carbide layer **24**, surrounding each second trench **38** there is a buffer layer **40** at the interface between the second trench **38** and the silicon carbide layer **24**. The buffer layer **40** is made of aluminum containing compound such as Aluminum Oxide (Al_2O_3) or Aluminum Nitride (AlN). In addition, adjacent second trenches **38** are separated from each other by a third higher barrier metal portion **42**. The plurality of third higher barrier metal portions **42** are deposited on the top surface of the silicon carbide layer **24** and are along the same horizontal line as the first high barrier metal portion **30**, the second high barrier metal portion **32**, and the plurality of first lower barrier metal portions **36**.

[0049] Note that the first trenches **26** are shown as separate parts in Fig. 1, but this is because Fig. 1 is a cross-sectional view of the diode structure. The two first trenches **26** are actually parts of a closed shape, and in particular an annual ring as shown in Fig. 2a and 2b. When the silicon carbide diode is viewed in any cross-section along a vertical plane, the resultant view would be identical or similar to that in Fig. 1. Similar to the first trenches **26**, the second lower barrier metal portion **34** are also parts of a single ring if viewed from top of the silicon carbide diode as shown in Figs. 2a and 2b. Similarly, any two second trenches **38** in Fig. 1 that are symmetrical around the active region are also parts of a single ring if viewed from top of the silicon carbide diode as shown in Figs. 2a and 2b. Figs. 2a and 2b show clearly that in this embodiment there are five of second trenches **38** in closed shapes, and more particular in annual ring shapes. These annual rings are concentric. The annual ring of the first trenches **26** (as represented by the first high barrier metal portion **30** / the second high barrier metal portion **32**) is also concentric with those rings of the second trenches **38**.

[0050] By implementing the above structure, the silicon carbide diode in this embodiment is particularly improved in its reversed breakdown voltage. Compared to traditional SiC diodes with 600V rating, the above silicon carbide diode can achieve a leakage current reduction greater than 40%, a blocking voltage improvement greater than 38%, but a manufacturing cost reduction by 44.2%. Such technical effects are achieved by the combination of the individual innovative features described above including but not limited to the first and second trenches, the combination of the lower barrier metal and higher barrier metal, the vertically offset lower barrier metal portions, the higher barrier metal portions between the second trenches, and the buffer layer around the second trench. However, it should be understood that each individual features can be used alone or in a limited combination with other features in other variations of the invention to achieve some effects, though not optimum. Below the performance improvements resulted by some of the individual features mentioned above will be explained.

[0051] Firstly, the hybrid Schottky structure in the silicon carbide diode of Figs. 1-2b contains both the higher barrier metal and the lower barrier metal, which achieves a good balance between the blocking voltage (reverse bias) and onset voltage (forward bias). The high barrier metal termination helps achieve a high blocking voltage, and the low barrier metal active region helps achieve a high forward current. Obviously, it is important to achieve both a high forward current for normal operation of the diode conducting status, and a high blocking voltage to avoid the diode from breakdown when it is reversibly biased. In the silicon carbide diode of Figs. 1-2, the higher barrier metal cap **22** provides terminations at the boundary of the active region so effectively the electrical field crowding may be reduced, thus reducing the leaking currents at the terminations. On the other side, different portions of lower barrier metal are deposited within the active region which help enabling a high forward current for the Schottky diode.

[0052] The arrangements of second trenches **38** outside the active region with dielectric materials, also help reduce the leakage current by reducing the electrical field crowding. Without the second trenches **38**, the leakage currents find a much easier way to enter the Schottky metals in the active region from the silicon carbide layer **24**. With the second trenches **38**, there is a resistivity increment (e.g. in the magnitude of 10^{15} Ohms) with the filled dielectric materials in the second trenches **38**, resulting in reduced leakage current. Therefore, there is less electrical field crowding at the termination of the active region of the silicon carbide diode.

[0053] In the silicon carbide diode above there are multiple rings of second trenches **38** and this further reduces the electrical field crowding at the terminations of the active region. Compared to the configuration of only one second trench **38**, the plurality of second trenches **38** could achieve a reduction of the electrical field strength by at least 61%.

[0054] In addition, the buffer layer **40** surrounding each second trench **38** in the silicon carbide diode above further decreases the leakage current on the basis of the second trench **38** itself already achieving this effect. Compared to conventional materials such as

SiO₂ that is used as a buffer material, the Aluminum compound such as Aluminum Oxide (Al₂O₃) or Aluminum Nitride (AlN) results in less gaps and defects between the atoms of Al and Oxygen, making them tightly packed, therefore greatly reducing the leakage current. The comparison between SiO₂ passivation and Al₂O₃ passivation in the silicon carbide diode in terms of reverse breakdown voltage and leakage current are shown in Figs. 3a and 3b respectively. By replacing the SiO₂ with the Al₂O₃ as passivation, the leakage current **73** in the case of SiO₂ is improved to the leakage current **72** in the case of Al₂O₃. The blocking voltage **71** in the case of SiO₂ which is less than 100V is significantly increased to being larger than 600V of the blocking voltage **70** in the case of Al₂O₃.

[0055] Turning to the active region, the silicon carbide diode in Figs. 1-2b contains multiple first trenches **26** of hybrid Schottky metals. As shown in Fig. 4, under a reverse bias condition of the silicon carbide diode, the high Schottky barrier created by the higher barrier metal at sidewalls **26a** of each first trench **26** creates a wider depletion region **48** in the silicon carbide layer **24**, which is pinched-off to adjacent first trenches **26**, and protects the plurality of first lower barrier metal portions **36** on the top surface of the silicon carbide layer **24**. This is because most reverse currents from the silicon carbide substrate **20** will flow through the higher barrier metal at the sidewalls **26a** of the first trenches **26** and also the second lower barrier metal portions **34** (where the current is represented by arrow **46**) at the bottom of the first trenches **26**. No or only a very small amount of reverse current (represented by arrow **48**) is passing through the plurality of first lower barrier metal portions **36** because of the high barrier metal depletion pinched-off protection.

[0056] Fig. 5a-5j show sequential steps of an exemplary method of how to produce the silicon carbide diode array in Figs. 1-2b. Note that the exemplary method described in this embodiment is not intended to be limiting, as the same silicon carbide diode may be produced using other methods, and/or with different sequences of the steps. The method starts in Fig. 5a in which a raw silicon carbide epi wafer which has been cleaned using the RCA clean procedures is prepared. The wafer comes with a silicon carbide substrate

20 of n+ type and a silicon carbide layer **24** on top thereof which is of n- type. Then, as shown in Fig. 5b, a layer of higher barrier metal **54** is deposited selectively on the top surface of the silicon carbide layer in a predetermined pattern. The results of the deposition include the third higher barrier metal portions **42** mentioned above, and also part of the higher barrier metal cap **22**. As mentioned above the third higher barrier metal portions **42** come in the shape of multiple concentric annual rings. Also, as shown in Fig. 5b the ohmic metal **28** is deposited on the bottom surface of the silicon carbide substrate **20** and forms the cathode of the silicon carbide diode.

[0057] Next, as shown in Fig. 5c the silicon carbide layer **24** goes through an etching process, resulting in parts of the silicon carbide layer **24** not covered by Schottky metal etched to form both first trenches **26** and second trenches **38**. As mentioned above the first trenches **26** and second trenches **38** come in the shape of concentric annual rings. Note that at this moment, nothing has been filled into first trenches **26** and second trenches **38**. After the trenches are formed, some of the Schottky metal (which is the higher barrier metal as mentioned above) are removed from the top surface of the silicon carbide layer **24**, and in particular on parts of the silicon carbide layer **24** between and surrounding the first trenches **26**. Next, in Fig. 5d, firstly a layer of Atomic layer deposited (ALD) dielectric **51** (e.g. Al_2O_3) is deposited on the top surface of the silicon carbide layer **24** including the first trenches **26**, the second trenches **38**, and the third higher barrier metal portions **42**, and then an oxide layer **50** is deposited on top of the dielectric layer **51**.

[0058] Next, in Fig. 5e the silicon carbide layer **24** undergoes an oxide Reactive Ion Etching (RIE) process by which the previously deposited dielectric **51** and oxide **50** on the top surface of the silicon carbide layer **24** are removed, but not all the dielectric **51** and oxide **50** inside the first trenches **26** and the second trenches **38**. Rather, there are residues of dielectric **51** and oxide **50** at the corner portions of the first trenches **26** (but not at the central area of the bottom of the first trenches **26**). In comparison, there are residues of dielectric **51** and oxide **50** at both the corner portions and actually the entire bottom of the second trenches **38**.

[0059] As shown in Fig. 5f, a layer of lower barrier metal **52** is deposited on the entire top surface of the silicon carbide layer **24** device, including the first trenches **26**, the second trenches **38**, and the third higher barrier metal portions **42**. The layer of lower barrier metal **52** then undergoes an annealing process. The layer of lower barrier metal **52** will react with the silicon carbide layer **24** if they contact directly with each other, but for portions of the carbide layer **24** which are covered by the oxide **50** then there is no such reaction. Next, as shown in Fig. 5g any unreacted lower barrier metal **52** are removed from the device, including essentially all such lower barrier metal **52** outside of the active region. Next, as shown in Fig. 5h spacers inside the first trenches **26** which are actually the residues of oxide **50** are removed so that only the second lower barrier metal portions **34** remain inside the first trenches **26**.

[0060] Consequently, as shown in Fig. 5i the higher barrier metal **54** is deposited on the active region of the device, patterned and then annealed, in order to fill the first trenches **26** and also to form the complete higher barrier metal cap **22**. Finally, as shown in Fig. 5j oxide **50** is deposited in the second trenches **38** and patterned so that the oxide **50** becomes dielectric materials fully filling up the second trenches **38** and has a top face flush with the top surface of the silicon carbide layer **24**. The silicon carbide diode is therefore manufactured.

[0061] Figs. 6a-6d show various other embodiments of the invention in which silicon carbide diodes are provided. For the sake of simplicity features of the silicon carbide diodes in Figs. 6a-6d that are identical or similar to those in Figs. 1-2b will not be described again herein. The silicon carbide diodes in Figs. 6a-6d basically contain less features than that in Figs. 1-2b, so their performance in terms of leakage current and reverse breakdown current are not so good as that of the silicon carbide diode in Figs. 1-2b. Also, note that the cross-sections of the silicon carbide diodes in In Figs. 6a-6b may not be illustrated in the same aspect ratio as that in Figs. 1-2b. In Fig. 6a, the silicon carbide diode contains no trench in the active region defined by the hybrid metals of a lower barrier metal **152** in the center and higher barrier metals **154** around the lower barrier metals **152**. The lower barrier metal **152** further contains no gap or separation but

rather it is an integral piece. Around the active region, there is a single ring of second trench **138** filled of dielectric material **150**. The silicon carbide diode in Fig. 6b has a structure very similar to that of Fig. 6a. However, the difference between Fig. 6b and Fig. 6a is that the trenches **238** in Fig. 6b outside of the active region is surrounded by a buffer layer **240** at an interface between the dielectric material **250** and the silicon carbide layer **224**. The silicon carbide diode in Fig. 6c is different from that in Fig. 6b in that it contains a plurality of trenches **338** within the silicon carbide layer **324** around the active region, with each of the trenches **338** having substantially the same dimension. Each trench **338** is filled with dielectric material **350** and is surrounded by a buffer layer **340**. The plurality of trenches **338** forms multiple concentric annual rings around the active region. There is a plurality of high barrier metal **342** formed in between any two of the plurality of trenches **338** such that the metals **342** form enclosed multiple concentric annual rings in a top view. The silicon carbide diode in Fig. 6d is different from that in Fig. 6a in that it contains a plurality of trenches **426** in the silicon carbide layer **424** which are located within the active region (which are similar to the first trench described with reference to Figs. 1-2b). Each trench **426** is filled with a higher barrier metal **454** and at the bottom of the trench **426** there is a layer of lower barrier metal **434**. The plurality of trenches **426** forms multiple concentric annual rings within the active region.

[0062] The exemplary embodiments of the present invention are thus fully described. Although the description referred to particular embodiments, it will be clear to one skilled in the art that the present invention may be practiced with variation of these specific details. Hence this invention should not be construed as limited to the embodiments set forth herein.

[0063] While the invention has been illustrated and described in detail in the drawings and foregoing description, the same is to be considered as illustrative and not restrictive in character, it being understood that only exemplary embodiments have been shown and described and do not limit the scope of the invention in any manner. It can be appreciated that any of the features described herein may be used with any embodiment. The illustrative embodiments are not exclusive of each other or of other embodiments not

recited herein. Accordingly, the invention also provides embodiments that comprise combinations of one or more of the illustrative embodiments described above. Modifications and variations of the invention as herein set forth can be made without departing from the spirit and scope thereof, and, therefore, only such limitations should be imposed as are indicated by the appended claims.

[0064] For example, the embodiments in Figs. 1-6d are silicon carbide diodes with different trenches, and/or barrier metals that form concentric annual rings if viewed from the top. However, those skilled in the art should realize that other types of closed shape may also be formed by the trenches and/or barrier metals, such as oval, eclipse, rectangle, etc.

[0065] In addition, the embodiment in Figs. 1-2b contains one ring of first trench, and five rings of second trenches, which all have roughly the same depth. Those skilled in the art can easily think of having different numbers of first trenches and/or second trenches in the silicon carbide diodes and they can have different dimensions than that in Figs. 1-2b. For example, instead of second trenches closer to the active region having a smaller width than those farther from the active region, it could be that all second trenches have uniform width.

What is claimed is:

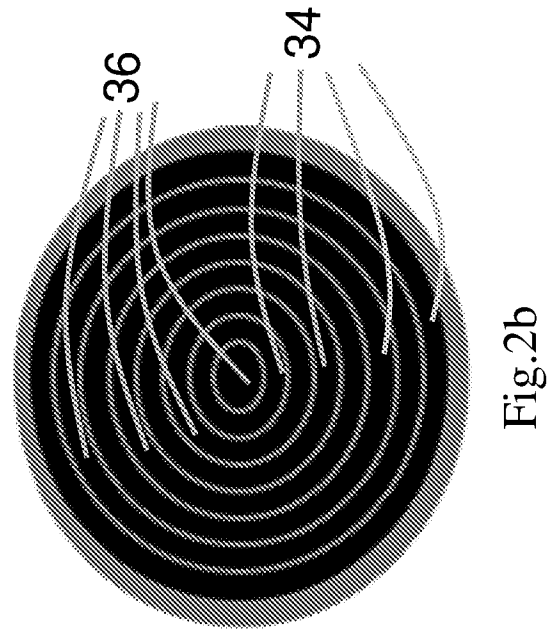
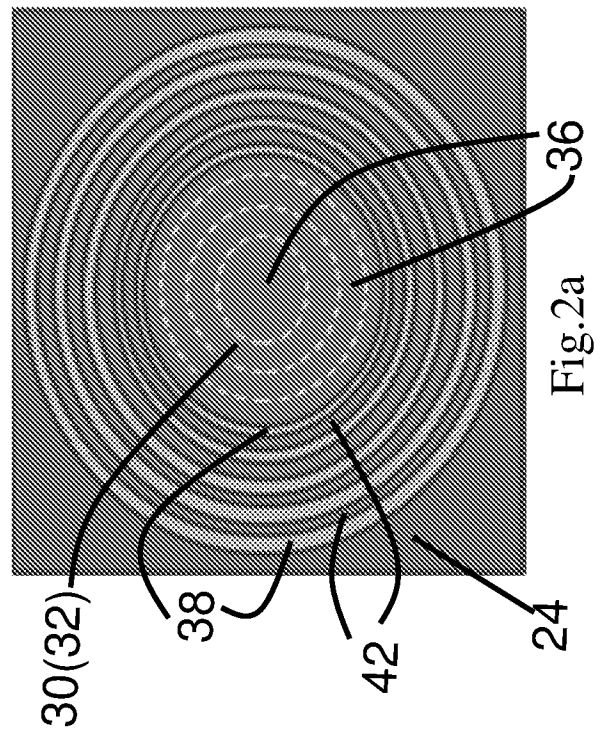
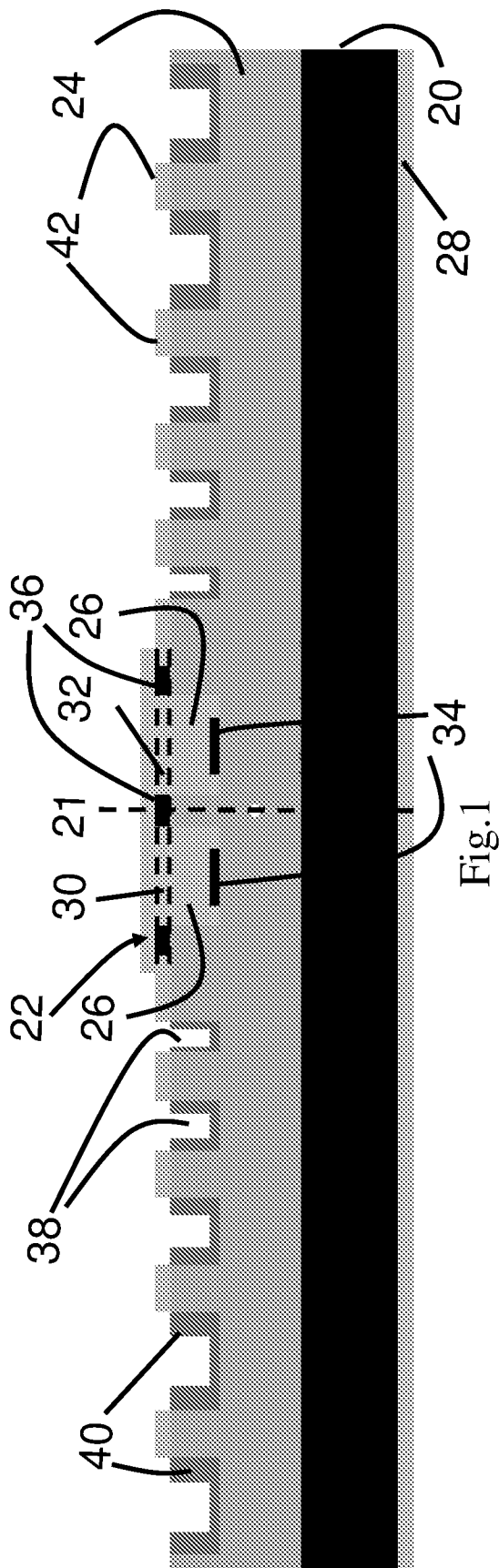
1. A silicon carbide diode, comprising:
 - a) a silicon carbide substrate;
 - b) a silicon carbide layer on top of the silicon carbide substrate, the silicon carbide layer being thinner and having lower doping than the silicon carbide substrate;
 - c) two first lower barrier metal portions disposed on the silicon carbide layer and separated from each other along a top surface of the silicon carbide layer;
 - d) a first higher barrier metal portion connected to the two lower barrier metal portions;wherein the first higher barrier metal portion is located between the two first lower barrier metal portions on the silicon carbide layer along a direction of the top surface of the silicon carbide layer.
2. The silicon carbide diode according to claim 1, further comprises a second higher barrier metal portion; the first and second higher barrier metal portions configured with the two first lower barrier metal portions in an alternating manner at the top surface of the silicon carbide layer, such that the first higher barrier metal portion and the second higher barrier metal portion are separated by one of the two first lower barrier metal portions.
3. The silicon carbide diode according to claim 2, wherein the first higher barrier metal portion and the second higher barrier metal portion further extend downwardly into the silicon carbide layer to form two first trenches.
4. The silicon carbide diode according to claim 3, further comprises second lower barrier metal portions located at the bottom ends of the first trenches.
5. The silicon carbide diode according to claim 1, further comprises a higher barrier metal cap, together with the silicon carbide layer, fully encapsulating the first lower barrier metal portions.
6. The silicon carbide diode according to claim 1, wherein the first higher barrier metal portion further extends downwardly into the silicon carbide layer to form a first trench.
7. The silicon carbide diode according to claim 1, further comprises a second trench separated from an active region defined by the first higher barrier metal portion and

the two first lower barrier metal portions; the second trench formed by a dielectric material.

8. The silicon carbide diode according to claim 7, further comprises a plurality of said second trenches which are separated from each other; each said second trench forming a closed shape when viewing from above.
9. The silicon carbide diode according to claim 8, wherein the plurality of said second trenches form a plurality of concentric rings.
10. The silicon carbide diode according to claim 8, wherein the plurality of said second trenches are separated from each other by one or more third higher barrier metal portions.
11. The silicon carbide diode according to claim 7, further comprises an aluminum compound buffer at an interface between the second trench and the silicon carbide layer.
12. A silicon carbide diode, comprising:
 - a) a silicon carbide substrate;
 - b) a silicon carbide layer on top of the silicon carbide substrate, the silicon carbide layer being thinner and having lower doping than the silicon carbide substrate;
 - c) an active region defined by at least one barrier metal which is formed on the silicon carbide layer; and
 - d) a plurality of trenches formed inside the silicon carbide layer, and separated from the active region along a direction of a top surface of the silicon carbide layer; wherein each said trench forming a closed shape when viewing from above; and each said trench formed by a dielectric material; and
 - e) a plurality of the barrier metal formed on the silicon carbide layer outside the active region; wherein each said barrier metal forming a closed shape and being located in between two of the plurality of trenches in when viewing from above.
13. The silicon carbide diode of claim 12, further comprises an aluminum compound buffer at an interface between the second trench and the silicon carbide layer.
14. A method of producing a silicon carbide diode, comprising the steps of:

- a) providing a silicon carbide layer on top of a silicon carbide substrate; the silicon carbide layer being thinner and having lower doping than the silicon carbide substrate;
 - b) forming a first trench and a second trench inside the silicon carbide layer; the first trench being part of an active region of the silicon carbide diode; the second trench separated from the first trench;
 - c) depositing a lower barrier metal on a top surface of the silicon carbide layer in the active region, which covers the first trench; and
 - d) depositing a higher barrier metal on the top surface of the silicon carbide layer in the active region, which covers the first trench.
15. The method according to claim 14, wherein step b) further comprises forming a plurality of second trenches that are separated from the first trench and from each other, each said second trench forming a closed shape.
16. The method according to claim 15, wherein step d) further comprises the depositing the higher barrier metal on portions of the silicon carbide layer surrounding openings of the plurality of second trenches.
17. The method according to claim 14, wherein step b) further comprises forming a plurality of first trenches that are separated from the second trench, and from each other by at least one portion of the silicon carbide layer.
18. The method according to claim 14, wherein step c) further comprises the step of depositing the lower barrier metal on a bottom surface of the first trench, as well as on portions of the silicon carbide layer surrounding an opening of the first trench.
19. The method according to claim 14, further comprises the step of filling the first trench with the higher barrier metal.
20. The method according to claim 14, further comprises the step of filling the second trench with a dielectric material.
21. The method according to claim 20, further comprises the step of forming a buffer layer at the interface between the second trench and the silicon carbide layer.

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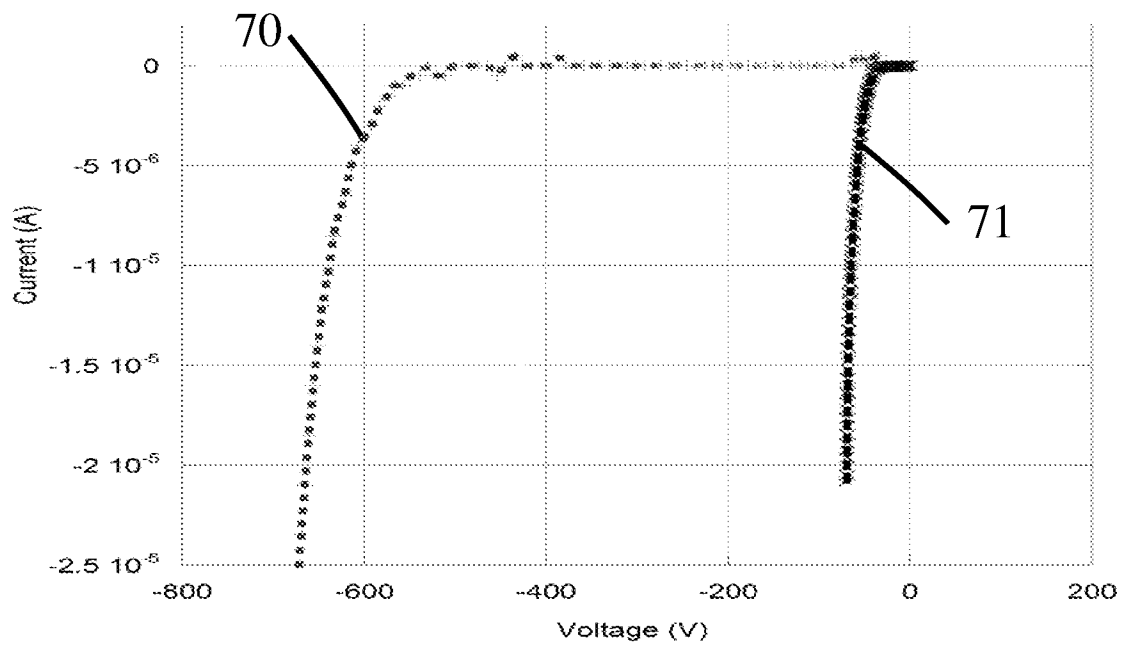


Fig.3a

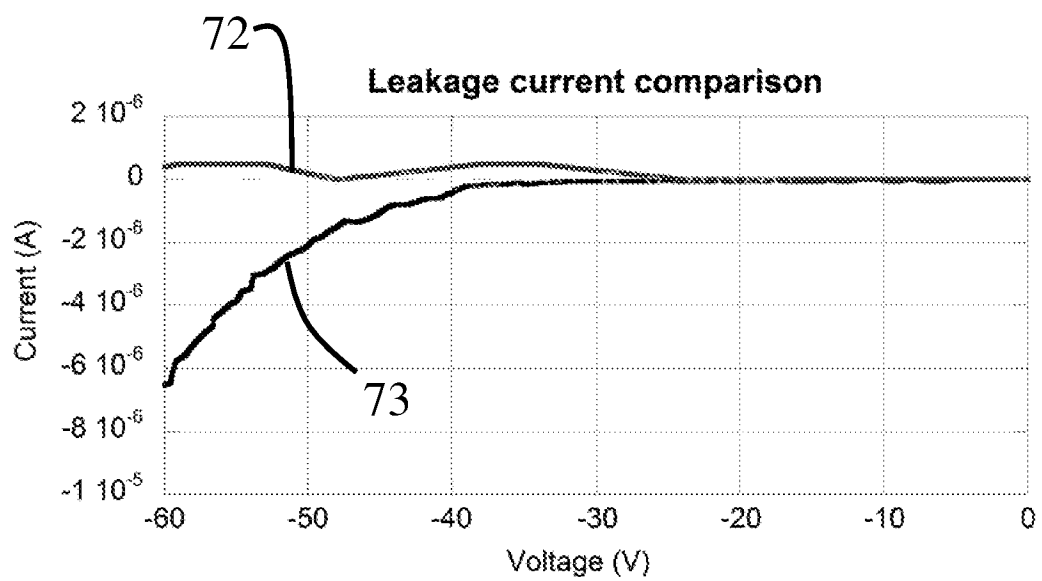


Fig.3b

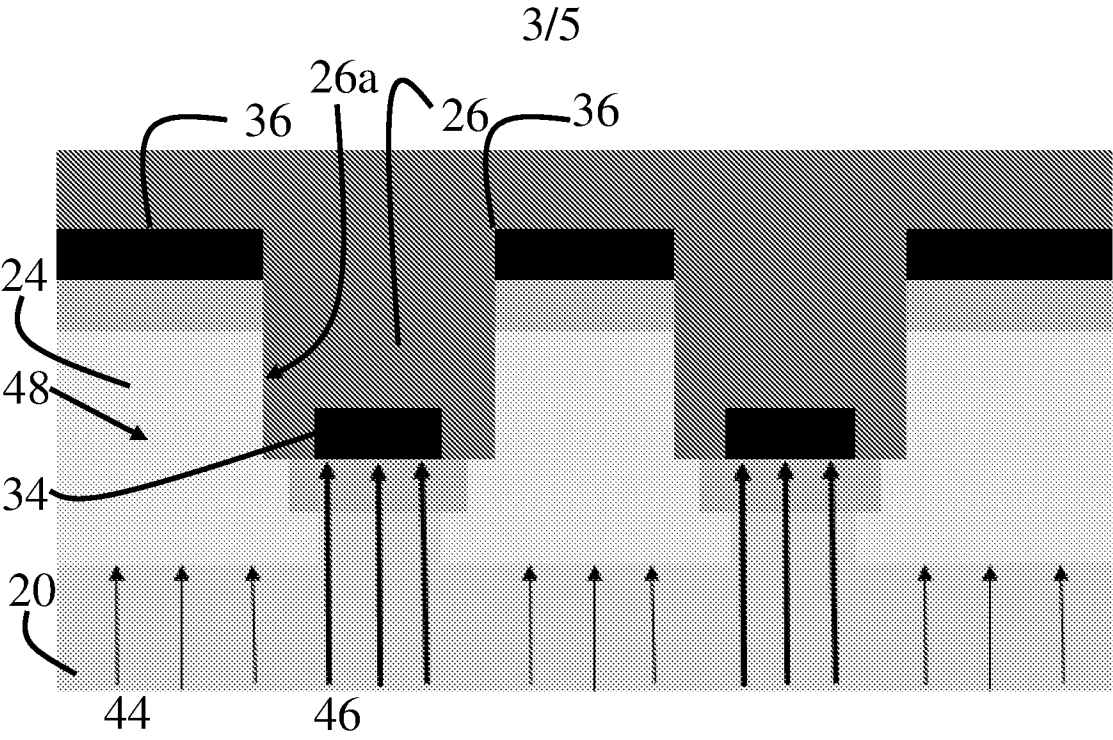
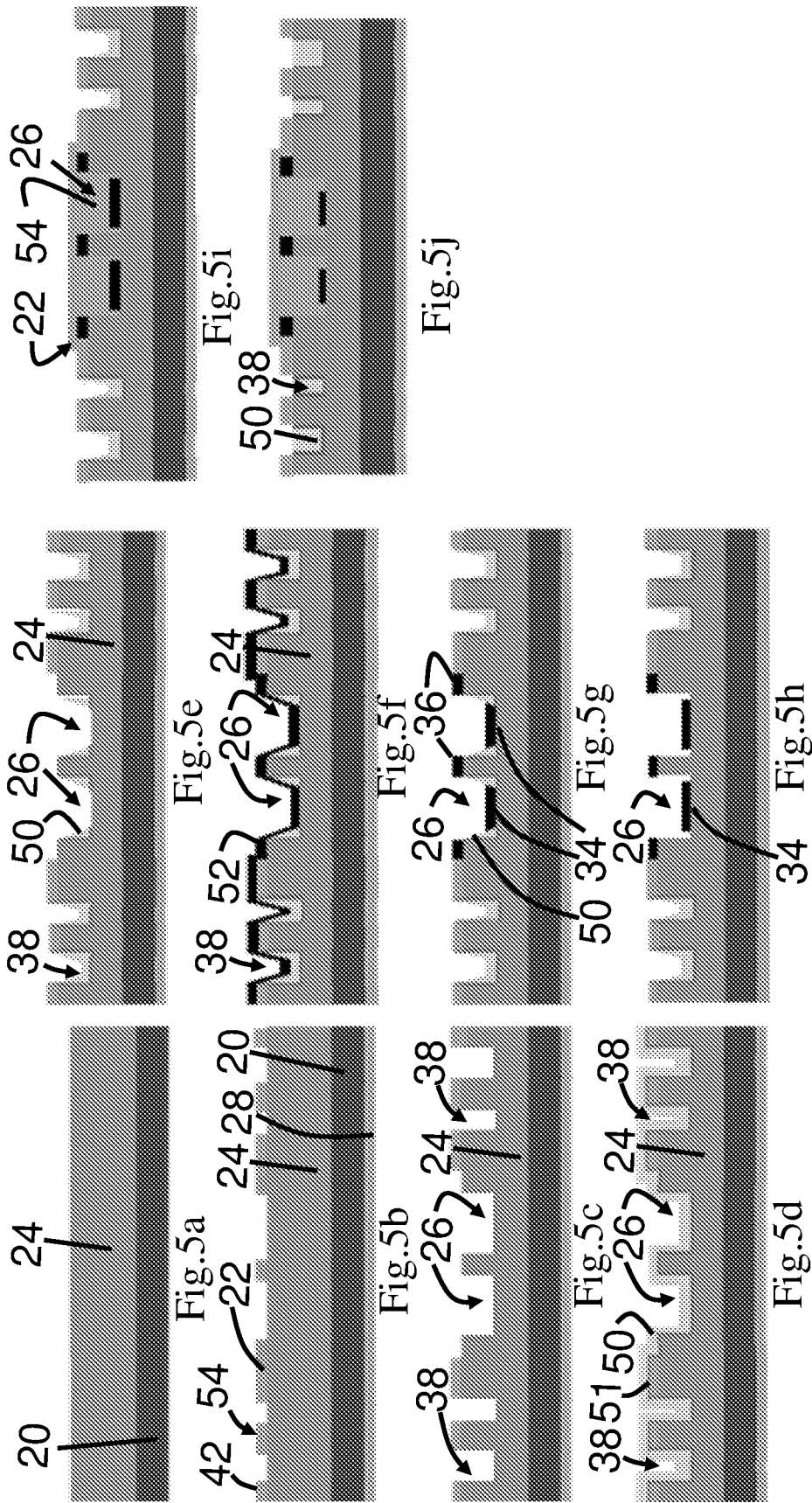


Fig.4



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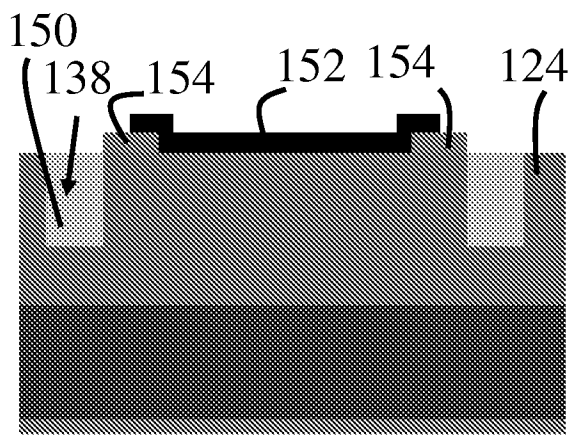


Fig.6a

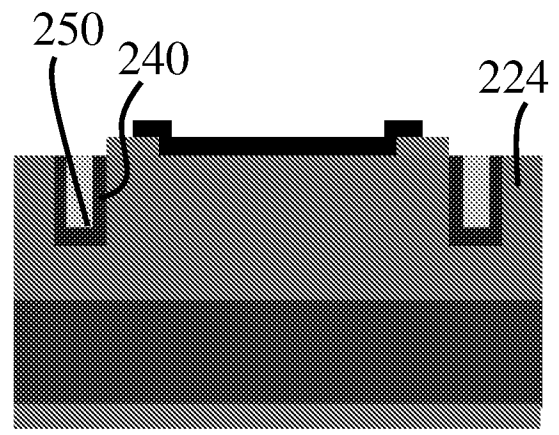


Fig.6b

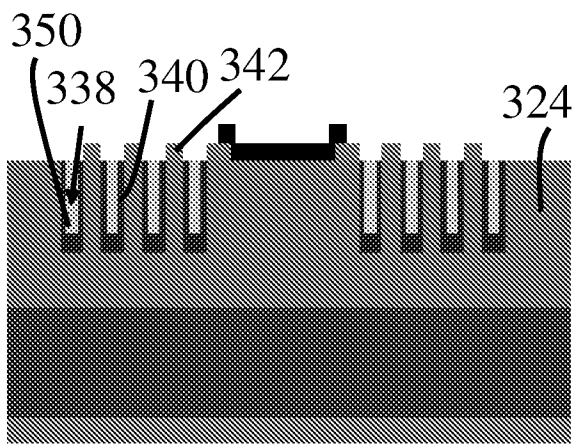


Fig.6c

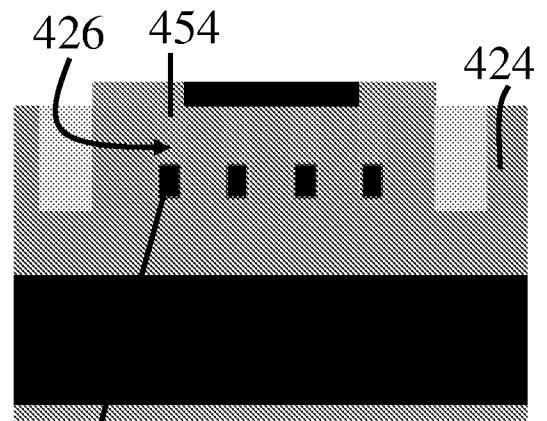


Fig.6d

INTERNATIONAL SEARCH REPORT

International application No.

PCT/CN2019/072016

A. CLASSIFICATION OF SUBJECT MATTER

H01L 29/872(2006.01)i; H01L 29/47(2006.01)i; H01L 21/04(2006.01)i

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

H01L

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

EPODOC, WPI, CNPAT, IEEE, CNKI: high voltage, silicon carbide, Schottky, high??, low??, large?, small??, barrier, metal, hybrid, trench

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	WO 2010132403 A1 (CREE, INC. ET AL.) 18 November 2010 (2010-11-18) description, paragraphs [0024]-[0028], [0040], [0051]-[0054]; figures 1, 10-11	1-2, 5
X	TW 415111 B (NATIONAL SCIENCE COUNCIL) 11 December 2000 (2000-12-11) description, page 7, line 17 - page 10, line 23; figures 1-4	1-2, 5
A	US 6362495 B1 (PURDUE RESEARCH FOUNDATION) 26 March 2002 (2002-03-26) the whole document	1-21
A	CN 108063090 A (BEIJING CENTURY GOLDRAY SEMICONDUCTOR CO., LTD.) 22 May 2018 (2018-05-22) the whole document	1-21



Further documents are listed in the continuation of Box C.



See patent family annex.

* Special categories of cited documents:

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“E” earlier application or patent but published on or after the international filing date

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“O” document referring to an oral disclosure, use, exhibition or other means

“P” document published prior to the international filing date but later than the priority date claimed

“T” later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

“X” document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

“Y” document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art

“&” document member of the same patent family

Date of the actual completion of the international search

11 September 2019

Date of mailing of the international search report

27 September 2019

Name and mailing address of the ISA/CN

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Facsimile No. (86-10)62019451

Telephone No. 86-(10)-53961393

INTERNATIONAL SEARCH REPORT
Information on patent family members

International application No.

PCT/CN2019/072016

Patent document cited in search report			Publication date (day/month/year)	Patent family member(s)			Publication date (day/month/year)
WO	2010132403	A1	18 November 2010	US	7915703	B2	29 March 2011
				US	2010289109	A1	18 November 2010
TW	415111	B	11 December 2000	None			
US	6362495	B1	26 March 2002	None			
CN	108063090	A	22 May 2018	None			